

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Reissue Application)
of U.S. Patent No. 6,329,275)
Issue Date: December 11, 2001) Group Art Unit: Unassigned
First Named Inventor: Takashi Ishigami) Examiner: Unassigned
Application No.: Unassigned)
Reissue Filing Date: December 10, 2003)
For: INTERCONNECTOR LINE OF)
THIN FILM, SPUTTER TARGET)
FOR FORMING THE WIRING)
FILM AND ELECTRONIC)
COMPONENT USING THE SAME)

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

PRELIMINARY AMENDMENT

Prior to the examination of the above reissue application, please amend this application as follows:

IN THE CLAIMS:

Please add claims 7-29 as follows:

7. (New) A sputter target consisting essentially of 0.001 to 30 at% of at least one first element selected from the group consisting of Y, Sc, La, Ce, Nd, Sm, Gd, Tb, Dy and Er, at least one second element selected from the group consisting of 0.01 at ppm to 3 at% of C with respect to the amount of the first element, 0.01 at ppm to 7.5 at% of O with respect to the amount of the first element, 0.01 at pm to